Supporting information

Porous graphene oxide based inverse spinel nickel ferrite nanocomposites for the enhanced adsorption removal of arsenic

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2. Materials and methods

2.1 Materials

All chemicals were of analytical grade and used as supplied in the present investigations. Graphite flakes procured from Sigma-Aldrich (USA) were used as a source for graphene oxide preparation in the present study. The stock solution (1000 mg/L) of both As(III) and As(V) was prepared from NaAsO₂ and Na₂HAsO₄·7H₂O, respectively. The reagents, Fe(NO₃)₃·9H₂O, Ni(NO₃)₃·9H₂O, HCl (40%), NH₄OH (56.6%), and H₂SO₄ (98%) were obtained from the Samchun Pure Chemicals Co. Ltd. (Korea); KMnO₄ and NaOH (98%) were purchased from Kanto Chemical Co. Inc. (Japan). NaNO₃ (98%), which was purchased from Duksan Pure Chemicals (Korea) and H₂O₂ (30%), which was supplied by Junsei Chemicals Co. Ltd. (Japan) were used in the preparation of GO, GONF and rGONF. The reducing agent, hydrazine hydrate supplied by Sigma-Aldrich (USA) was used for the reduction of GONF. 0.1 M NaNO₃, NaCl, Na₂SO₄, NaF, Na₂CO₃ and Na₃PO₄·12H₂O (Purchased from Samchun Pure Chemicals Co. Ltd. (Korea)) in deionized water, respectively. These solutions were further diluted to suitable concentrations on the day of use.

2.2 Characterization of GONF and rGONF nanocomposites

The crystalline nature and size of the prepared GONF and rGONF nanocomposites were confirmed by X-ray powderdiffraction (XRD) analysis using Rigaku D/Max-2500 X-ray diffract meter (Japan). Spectrum GX & Auto image Fourier Transform Infrared Spectroscopy (FT-IR) (Perkin-Elmer, USA) was used for analyzing the functional groups of GONF and rGONF. ESCALAB-210 (Spain) X-ray photoelectron spectroscopy (XPS) was used for elemental composition analysis of the prepared GONF and rGONF samples. S-4300 & EDX-350 (Hitachi, Japan) was used for the measuring surface morphology and composition of samples. Autosorb-1, Quanta chrome instrument (USA) was used to measure the Brunauer, Emmett and Teller (BET) surface area and pore sizes of GONF and rGONF. Veeco Inc., (New York) atomic force microscopy (AFM) imaging was used to capture AFM-images of GONF and rGONF. Sonics Vibracell (CV 334, USA) was used for the ultrasonification of GO, GONF, and rGONF. Magnetic measurements of GONF and rGONF were performed using a SQUID magnetometer (MPMS-7, Quantum Design, USA). All pH measurements were taken using a 340i pH meter (WTW, Germany). The solution pH was adjusted using HCl and NaOH (0.1 mol/L) solutions. The arsenic concentration in aqueous solution was determined using Optima 2100 DV inductive coupled plasma-optical emission spectroscopy (ICP-OES) (Perkin-Elmer, USA) equipped with auto sampler.

Results and discussion

3.2 Adsorption studies of As(III) and As(V) onto GONF and rGONF

Kinetic models

Pseudo-first and pseudo-second model

The linear form of pseudo first-order rate equation is

$$Log(q_e - q_t) = Log q_e - k_1 t$$

A linear form of pseudo second-order kinetic model is express by eq. (2)

$$t/q_t = 1/(k_2 q_e^2) + t/q_e$$

where q_e and q_t are the amounts of arsenic adsorbed (mg/g) at equilibrium and time $t(\min)$, respectively; $k_1(\min^{-1})$ and $k_2(g \cdot mg^{-1} \cdot min^{-1})$ are the rate constant of the pseudo first-order and pseudo second-order kinetic models, respectively, for adsorption process.

(1)

(2)

Weber-Morris kinetics model

Intra-particle mass transfer diffusion model proposed by Weber and Morris can be written as follows:

$$q = k_i t^{1/2} + C \tag{3}$$

where C (mg/g) is the intercept and ki is the intra-particle diffusion rate constant(g·mg⁻¹·min^{-0.5}) for adsorption.

Boyd model

Boyd model has the following form:

$$Bt = -\ln(1-q_t/q_e) - 0.4977$$

where q_t and q_e are the amounts of dyes adsorbed on the adsorbent (mg·g⁻¹) at time t(min) and at equilibrium time (minute), respectively; $B = \pi^2 D_i / r^2$ (*Di* is the effective diffusion coefficient of

(4)

the adsorbate and r is the radius of adsorbent particlesassumed to be spherical).

Table S1 Physical and chemical compositions of real ground water collected from Hagye-dong, Nowon-gu, Seoul, RO Korea (N=3, mean values reported here, the standard deviation is less than 5%)

Physical or chemical compositions	Value or concentration	
pH	6.58	
ORP	161.3 mv	
DO	5.98 mg/L	
EC	0.701 ms/cm	
Ca ²⁺	28.96 mg/L	
Na ⁺	13.31 mg/L	
K ⁺	1.72 mg/L	
Mg^{2+}	3.62 mg/L	
Cl-	29.29 mg/L	
NO ₃ -	36.05 mg/L	
SO4 ²⁻	26.13 mg/L	
F-	Not detected	
$As^{3+} or As^{5+}$	Not detected	

Table S2 BET adsorption surface analysis results for GO, rGO, GONF and rGONFnanocomposites (N=4, number of measurements)

Characteristics	Nanocomposites materials			
	GO	rGO	GONF	rGONF
Surface area, m ² /g	2.59	21.02	122.74	167.26
BET surface area, m ² /g	2.81	21.13	135.99	174.14
Langmuir surface area, m ² /g	3.97	26.59	198.79	240.35
Pore volume, cm ³ /g	0.01	0.07	0.12	0.24
Pore size, nm	14.34	12.62	3.42	5.59
Particle size, nm	1000	284.00	44.12	34.46

Figure captions

Fig. S1 XRD and FT-IR pattern for GO, GONF and rGONF nanocomposites prepared in the present study.

Fig. S2 Scanning electron microscopy (SEM) images for GO and its nanocomposites, GONF and rGONF.

Fig. S3 N₂ adsorption desorption isotherms of GONF and rGONF measured by BET analysis.

Fig. S4 Photo image of water dispersed nanocomposites, GONF and rGONF and their separation by external magnetic field.

Fig. S5 Studies of ionic strength effect on adsorption of As(III) and As(V) with GONF and rGONF by using NaCl, KCl, NaNO₃, CaCl₂ and MgCl₂ (0.005 to 0.5 mol/L).



Fig. S1



Fig. S2







Before applied external magnetic field

After applied external magnetic field





